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## 磁気共鳴力顕微鏡用シリコンナノワイヤーカンチレバー

Silicon Nanowire cantilever for Magnetic Resonance Force Microscopy

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**Introduction:** Magnetic resonance force microscopy (MRFM) is a magnetic resonance imaging technique based on scanning probe microscopy. In terms of force sensitivity, the structure of the cantilevered sensor should be narrower [1]. Recently, Si nanowire cantilevers with a high quality factor have been reported for use of force detection [2]. In this research, Si nanowire cantilevers have been developed for MRFM. The key of the research is the batch fabrication process with the design of a magnetic material (nickel) on the cantilever.

**Experiments:** The Si nanowire cantilevers are fabricated from a silicon on insulator wafer with a 200nm-thick device layer. The nanocantilever structure is patterned by electron beam lithography, and the top Si layer is etched by fast atom beam using  $SF_6$  gas, a 500-nm-thick nickel layer is deposited using DC facing targets sputtering, and magnet pattern is formed by lift-off process. The handling Si is etched from the back side using deep reactive ion etching. The box-layer of SiO<sub>2</sub> is etched and the structure is released by vapor HF etching.

**Results:** The successfully fabricated Si nanowire cantilever (width: 150nm, length: 50  $\mu$ m) with nickel pattern is shown in Fig. 1. The resonance frequency of the Si nanowire cantilever is measured by laser Doppler vibrometer in vacuum (< 10<sup>-2</sup> Pa) as shown in Fig. 2. The resonance frequency of the Si nanowire cantilever is 8.006 kHz with 5000 of Q factor (Fig. 3). At the room temperature, the minimum detectable force of the SiNW-cantilever is calculated to be 1.9 x 10<sup>-16</sup> N. The Si nanowire cantilever with nickel magnet has been successfully fabricated with top-down fabrication process. We believe that this development will provide a molecular imaging by MRFM.

<sup>[2]</sup> Neil E. Jenkins, Lauren P. De Flores, Jack Allen, Tse Nga Ng, Sean R. Garner, Seppe Kuehn, Jahan M. Dawlaty, and John A. Marohn, J. Vac. Sci. Technol. B, 22(3), (2004) 909



<sup>[1]</sup> T. D. Stowe, K. Yasumura, T. W. Kenny, D. Botkin, K. Wago, D. Botkin, K. Wago, and D. Rugar, Appl. Phys. Lett., 71, (1997) 288